

Category	Tool	Tool Location	Tool Phone	Primary	Phone	Secondary	Phone
Lithography	JEOL E-beam	216/G107	x76237	Marc Cangemi	301-975-5993	Rich Kasica	301-975-2693
	JEOL E-beam Cleanroom	215/A101	x8221	Marc Cangemi	301-975-5993	Rich Kasica	301-975-2693
	Zeiss FIB Raith Elphy	216/G103	x2012	Kerry Siebein	301-975-8458	Rich Kasica	301-975-2693
	ASML Stepper	215/A105	x3224	Rich Kasica	301-975-2693	Liya Yu	301-975-4590
	ASML Design Station	215/A105	x3224	Rich Kasica	301-975-2693	Liya Yu	301-975-4590
	Nano-imprinter	215/A103	x2391	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	Laser Writer	215/A103	x2391	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	Maskless Aligner	215/A105	x3224	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	SussMA6	215/A102	x2119	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	SussMA8	215/A102	x2119	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	Suss Resist Developer	215/A105	x3224	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	Suss Resist Coater	215/A105	x3224	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	Brewer Science Resist Spinners	215/A102	x2119	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	HMDS Prime	215/A102	x2119	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
Photoresist Stabilization System	215/A105	x3224	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993	
Physical Vapor Deposition	4Wave Cluster Sputter	215/A104	x3196	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
	Sputter 1	215/B104	x3574	Gerard Henein	301-975-5645	Marc Cangemi	301-975-5993
	Sputter 2	215/B104	x3574	Gerard Henein	301-975-5645	Marc Cangemi	301-975-5993
	E-Beam Evap 1	215/B104	x3574	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
	E-Beam Evap 2	215/B104	x3574	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
	Parylene Deposition	215/B104	x3574	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
Chemical Vapor Deposition	Atomic Layer Deposition	215/A106	x3557	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	PECVD	215/B106	x5332	Rich Kasica	301-975-2693	Rich Kasica	301-975-2693
	Molecular Vapor Coater	215/A103	x2391	Lei Chen	301-975-2908	Rich Kasica	301-975-2693
Dry Etch	SPTS Deep Si Etch	215/B105	x3583	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	Unaxis Deep Si Etcher	215/B105	x3583	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	Unaxis ICP Etcher	215/B105	x3583	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	Oxford Etcher 1	215/A106	x3557	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	Oxford Etcher 2	215/A106	x3557	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	Unaxis RIE 1	215/B105	x3583	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	Unaxis RIE 2	215/B105	x3583	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	Ion Mill	215/A106	x3557	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
	XeF2 Silicon Etcher	215/B105	x3583	Lei Chen	301-975-2908	Gerard Henein	301-975-5645
	SPTS HF Vapor Etcher	215/B102	x6088	Rich Kasica	301-975-2693	Liya Yu	301-975-4590
Downstream Asher	215/B105	x3583	Lei Chen	301-975-2908	Gerard Henein	301-975-5645	
Imaging and Analysis	TITAN TEM	216/G115	x6082	Alline Myers	301-975-3775	Kerry Siebein	301-975-8458
	ZEISS FESEM	215/A101	x8221	Kerry Siebein	301-975-8458	Joshua Schumacher	301-975-8065
	JEOL FESEM	215/D106	x70052	Kerry Siebein	301-975-8458	Joshua Schumacher	301-975-8065
	NanoMill	216/G101	x8633	Alline Myers	301-975-3775	Kerry Siebein	301-975-8458
	Leica EM GP	216/G101	x8633	Alline Myers	301-975-3775	Kerry Siebein	301-975-8458
	Bruker AFM	215/B103	x2528	Rich Kasica	301-975-2693	Lei Chen	301-975-2908
	Asylum AFM	215/C002-2	x6090	Kerry Siebein	301-975-8458	Lei Chen	301-975-2908
Focused Ion Beams	FEI FIB 1	216/G113	x5302	Joshua Schumacher	301-975-8065	Kerry Siebein	301-975-8458
	FEI FIB 2	216/G113	x5302	Joshua Schumacher	301-975-8065	Alline Myers	301-975-3775
	ZEISS FIB	216/G103	x2012	Kerry Siebein	301-975-8458	Joshua Schumacher	301-975-8065
Metrology	Wyatt DLS	216/G101	x8633	Joshua Schumacher	301-975-8065	Kerry Siebein	301-975-8458
	XRD	216/G103	x2012	Kerry Siebein	301-975-8458	Gerard Henein	301-975-5645
	Film Stress	215/B103	x2528	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
	Goniometer	215/B103	x2528	Lei Chen	301-975-2908	Marc Cangemi	301-975-5993
	Ellipsometer	215/B103	x2528	Marc Cangemi	301-975-5993	Lei Chen	301-975-2908
	Filmetrics F40-UV	215/B103	x2528	Marc Cangemi	301-975-5993	Lei Chen	301-975-2908
	Filmetrics F20	215/B103	x2528	Marc Cangemi	301-975-5993	Lei Chen	301-975-2908
	NanoSpec	215/B103	x2528	Marc Cangemi	301-975-5993	Lei Chen	301-975-2908
	Dektak 6M	216/F108					
	Dektak XT 1	215/B103	x2528	Gerard Henein	301-975-5645	Marc Cangemi	301-975-5993
	Dektak XT 2	215/B103	x2528	Gerard Henein	301-975-5645	Marc Cangemi	301-975-5993
	Parametric Test	215/B106	x5332	Liya Yu	301-975-4590	Matt Robinson	301-975-2421
	Four Dimensions 4pt Probe	215/A106	x3557	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
	Hall Effect	215/C02-2	x6090	Rich Kasica	301-975-2693	Gerard Henein	301-975-5645
	Jandel 4pt Probe	215/A106	x3557	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
CD Microscope	215/A102	x2119	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993	
Speciality Tools	Wafer Bonder	215/A102	x2119	Liya Yu	301-975-4590	Lei Chen	301-975-2908
	Critical Point Dryer 1	215/A102	x2119	Marc Cangemi	301-975-5993	Rich Kasica	301-975-2693
	Critical Point Dryer 2	215/B101	x3342	Marc Cangemi	301-975-5993	Rich Kasica	301-975-2693
	CMP	215/C02-2	x6090	Gerard Henein	301-975-5645	Lei Chen	301-975-2908
Soft Lithography	PDMS Casting Station	216/F102	x4033	Matt Robinson	301-975-2421	Joshua Schumacher	301-975-8065
	Assembly Hood	216/F102	x4033	Matt Robinson	301-975-2421	Joshua Schumacher	301-975-8065
	Plasma Bonder	216/F102	x4033	Matt Robinson	301-975-2421	Joshua Schumacher	301-975-8065
	Forced Convection Curing Oven	216/F102	x4033	Matt Robinson	301-975-2421	Joshua Schumacher	301-975-8065
	Silanization Oven	216/F102	x4033	Matt Robinson	301-975-2421	Joshua Schumacher	301-975-8065
	Microfluidic Test Station	216/F102	x4033	Matt Robinson	301-975-2421	Joshua Schumacher	301-975-8065
High Purity Furnace	High Purity Wet Ox	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	High Purity Dry Ox	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	High Purity Sinter	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	High Purity Doping	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
LPCVD	SiN LPCVD	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	Poly LPCVD	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	LTO LPCVD	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
Gen Furnaces	Gen. Wet Ox	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	Gen. Dry Ox	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	Sinter	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	Anneal	215/B106	x5332	Rich Kasica	301-975-2693	Matt Robinson	301-975-2421
	AnnealSys RTA	215/B105	x3583	Gerard Henein	301-975-5645	Rich Kasica	301-975-2693
Wet Chemistry	Spray Clean Tools	215/A102	x2119	Matt Robinson	301-975-2421	Liya Yu	301-975-4590
	Metal Liftoff	215/A102	x2119	Marc Cangemi	301-975-5993	Liya Yu	301-975-4590
	General Chem Acid Hood	215/B101	x3342	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	General Chem Solvent Hood	215/B101	x3342	Liya Yu	301-975-4590	Marc Cangemi	301-975-5993
	Lithography Solvent Hoods	215/A104	x3196	Rich Kasica	301-975-2693	Marc Cangemi	301-975-5993
Packaging	Dicing Saw	215/C002-2	x6090	Gerard Henein	301-975-5645	Liya Yu	301-975-4590
	Gold Wire Bonder	215/C002-2	x6090	Gerard Henein	301-975-5645	Joshua Schumacher	301-975-8065
	Aluminum Wire Bonder	215/C002-2	x6090	Gerard Henein	301-975-5645	Joshua Schumacher	301-975-8065
	Flip Chip Bonder	215/C002-2	x6090	Gerard Henein	301-975-5645	Joshua Schumacher	301-975-8065
Access	PDMS Lab	216/F102	x4033	Matt Robinson	301-975-2421	Joshua Schumacher	301-975-8065
	Surface Analysis Lab	216/F108		Kerry Siebein	301-975-8458	Alline Myers	301-975-3775
	EM Sample Prep Lab	216/F110		Alline Myers	301-975-3775	Kerry Siebein	301-975-8458
	Sample Prep Lab	216/G101	x8633	Alline Myers	301-975-3775	Kerry Siebein	301-975-8458